



# Hydrogenation of Long Wavelength Infrared Focal Plane Arrays Based on Type II Superlattices

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# Motivation and Opportunities



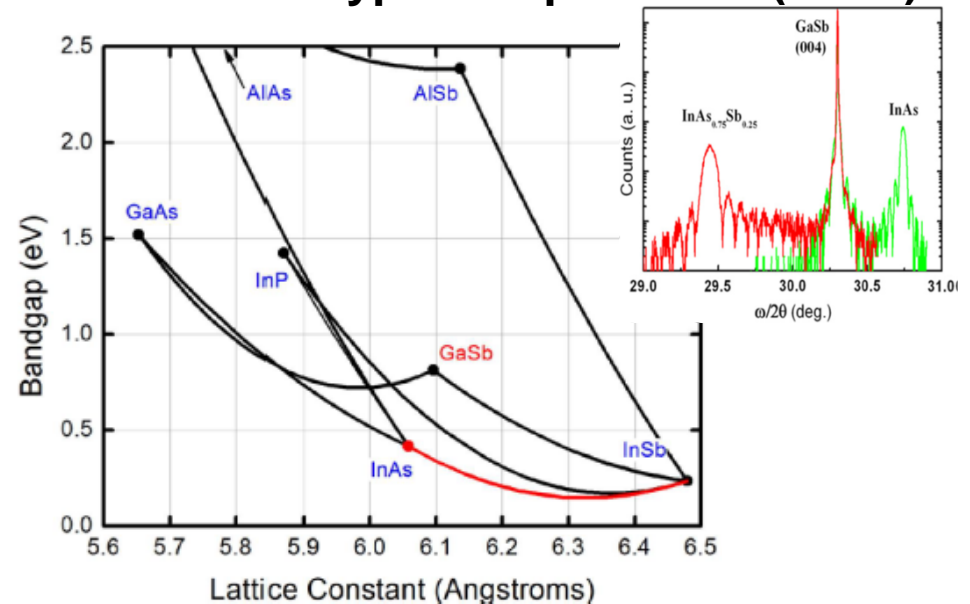
## Requirements

- Broad spectral response
- Large format focal plane arrays (FPAs)
- Improved operability
- Higher sensitivity
- Higher operating temperature

## Limitations

- Surface passivation problematic
- Longer wavelengths require higher Sb content, which adds strain
- Shockley-Read-Hall (SRH) lifetimes dominate below ~150 K
- Absorption coefficient in two-layer superlattices < HgCdTe

## InAs/InAsSb Type 2 Superlattice (T2SL)



- GaSb substrates readily available
- May be strain-balanced for growth on GaSb substrates
- Broad spectral response (2-20  $\mu\text{m}$ )
- Electron effective mass > HgCdTe: should reduce tunneling current
- Smaller Auger coefficient (longer Auger lifetime) than HgCdTe



# Technical Background



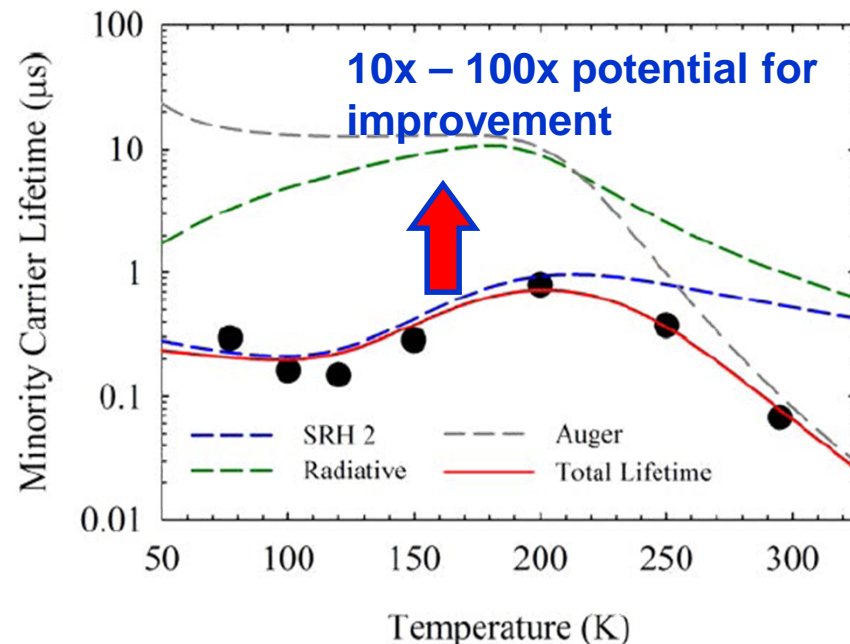
## Key Material Properties

- Minority carrier lifetime
- Minority carrier diffusion length
- Absorption

- Dark current
- Noise
- Spectral response
- QE

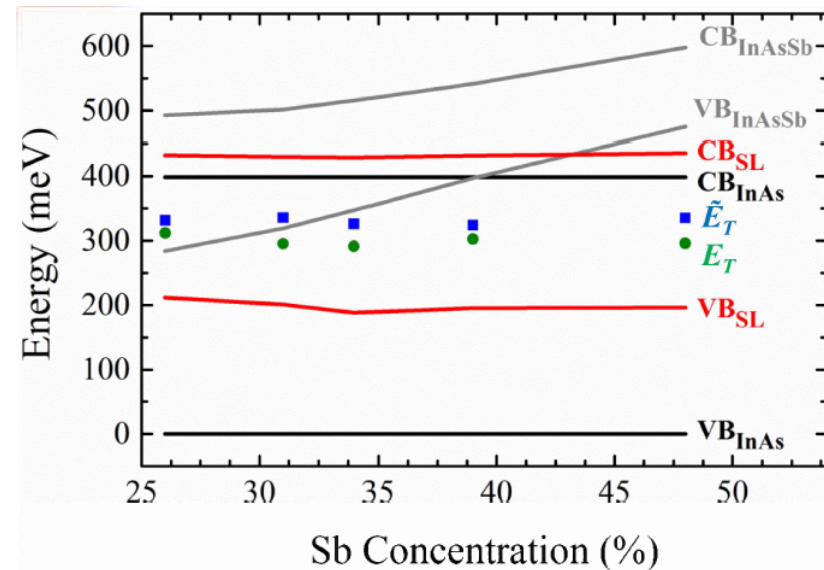
- Sensitivity
- Detectivity
- Operating temperature

T2SL carrier lifetime:  $\sim 10 \mu\text{s}$ , 100 – 200 K  
Limited by SRH (defects)



Olson, et al., Appl. Phys. Lett. 103, 052106 (2013)

InAs/InAsSb defects create mid-gap states



Aytac, et al., Appl. Phys. Lett. 105, 022107 (2014)

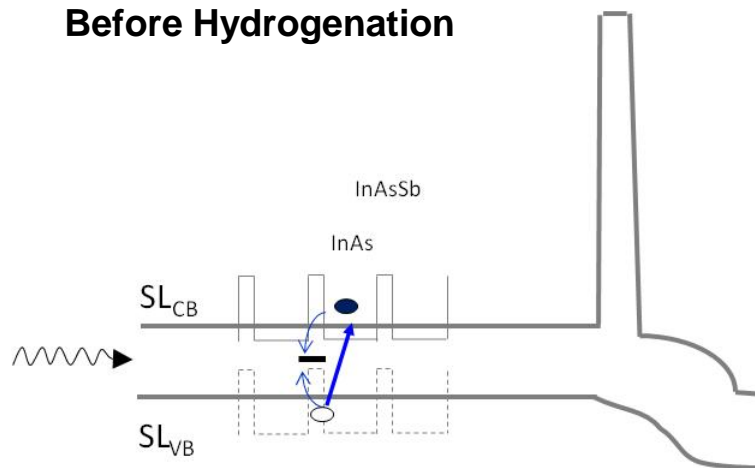


# Effects of Hydrogenation



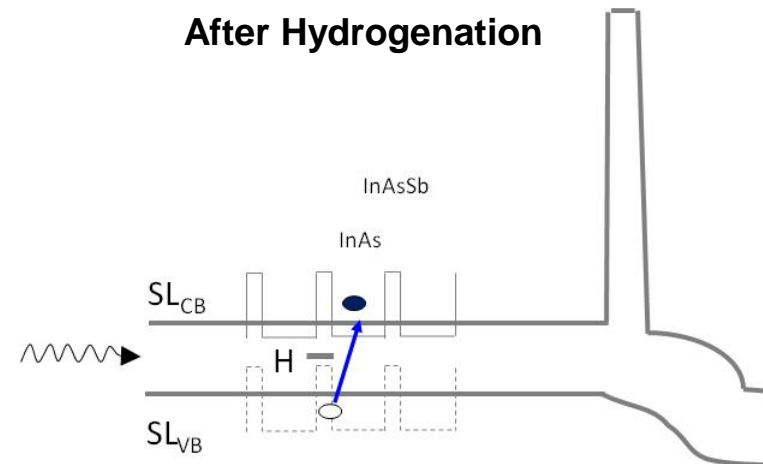
- Inductively coupled plasma (ICP) hydrogen can be introduced into molecular beam epitaxy (MBE) films, photodiodes, and detector arrays
- Dangling bonds around defects give rise to states in the band gap acting as SRH generation/recombination centers.
- Hydrogen attaches to dangling bond, forms electrically inactive bonding and antibonding states
- Reducing the electrical activity of defects is equivalent to lowering the density of defects
- Innovative plasma-assisted hydrogenation technique may improve FPA performance:
  - Lower residual nonuniformity
  - Increased operability
  - Increased detectivity

**Before Hydrogenation**



Loss of photogenerated carriers through scattering and recombination

**After Hydrogenation**



Atomic hydrogen introduced by ICP renders inactive the scattering and recombination centers – photocarriers are collected



## Hydrogenation of Si

- Locations in Si crystals:
  - Bound to a dangling bond at a defect site
  - Molecular hydrogen ( $H_2$ )
  - Atomic hydrogen (M site)
- Staebler-Wronski effect in polycrystalline solar cells
- Passivates impurities
- Deactivates donor and acceptors
- Si-H, Si-H<sub>2</sub>, and Si-H<sub>3</sub> bonds on Si surfaces

## Hydrogenation of III-V Crystals

- Exceptional stability of the {Mg,H} pair has long prevented the p-type doping of GaN
- Hydrogen passivation of dislocation cores in GaN
  - Reduced leakage currents
  - Enhanced LED and laser diode performance
- Hydrogen passivates the prevalent (EL2) deep-level As antisite ( $As_{Ga}$ ) donor defects in GaAs, reducing compensation

Si Impurity susceptible to H <sup>+</sup> /levels	E (eV)
Au, E(0.54) H(0.35)	2.3
Pd, E(0.22) H(0.32)	2.4
Pt, E(0.28)	2.3
Cu, H(0.20, 0.35, 0.53)	2.5
Ni, H(0.18, 0.21, 0.33)	2.5
Ag, E(0.54) H(0.29)	2.2
Fe, H(0.32, 0.39)	1.5
O-V, E(0.18)	1.9
V-V, E(0.22)	1.9
Laser, E(0.19, 0.3)	2.4
Sputter etching	1.8
Plastic deformation	3.1
Grain boundaries	2.5
Chalcogenides (S, Se, Te)	> 1.1

## Hydrogenation of Chalcogenides

- Hydrogen in LPE HgCdTe reduces surface trap states and passivates Hg vacancies, but activity restored after 70°C anneal
- Density functional theory predicts multiple hydrogen atoms attaching to a mercury vacancy; more likely than single atoms
- Cu, Ag, N<sub>2</sub> and Li in CdTe



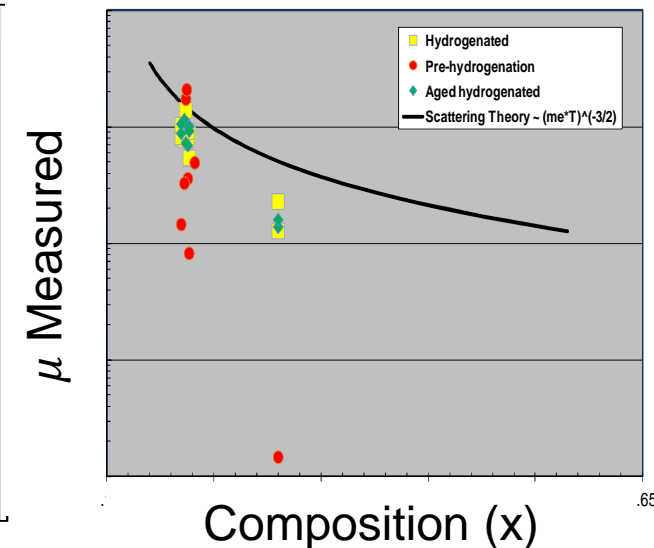
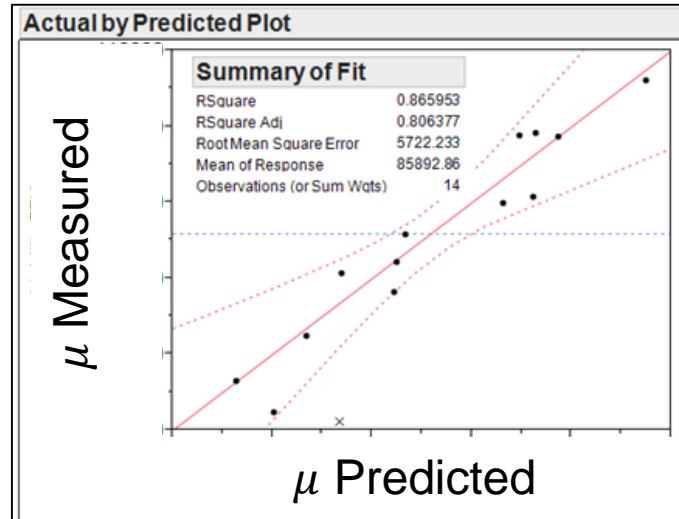
# ICP Hydrogenation of HgCdTe



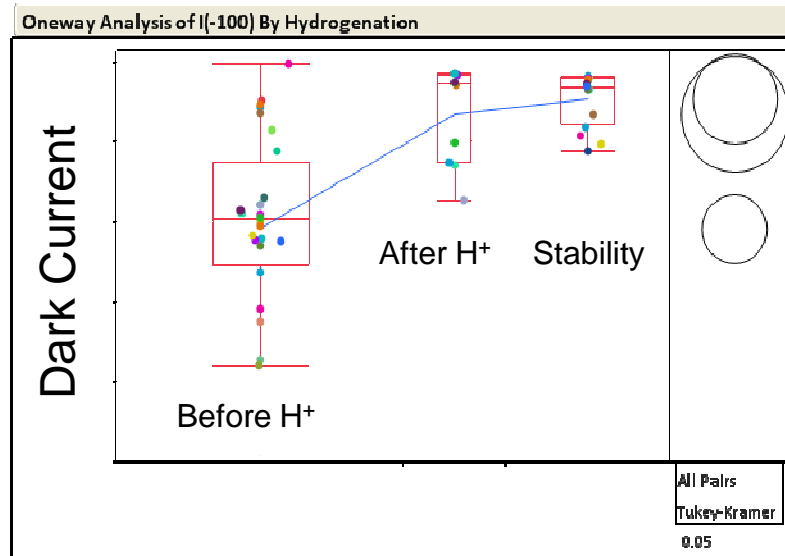
## Hall mobility analysis reveals key ICP parameters

- Atomic hydrogen used in Si and GaAs
- Hydrogen passivation of dislocation cores in GaN reduces leakage currents and enhances LED and laser diode performance
- In HgCdTe: reduced surface trap states and passivated  $V_{Hg}$
- Passivates deep defects, but restored after 70°C anneal
- Prior work at EPIR Technologies:

- $H^+$  reduces scattering and recombination in ICP exposed HgCdTe
- Photoassisted methods used for HgCdTe, but films and passivations degrade after UV exposure



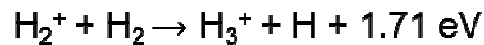
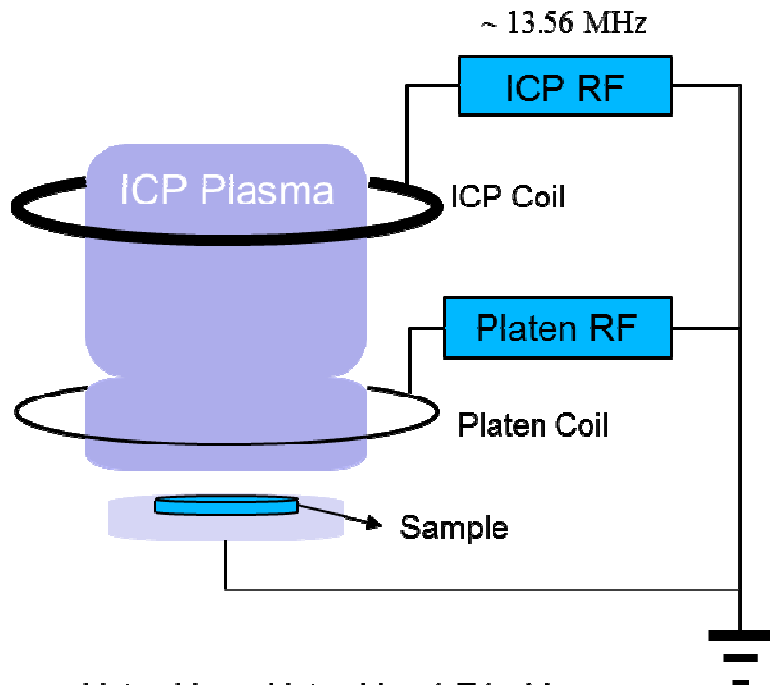
## Dark current reduction after ICP hydrogenation



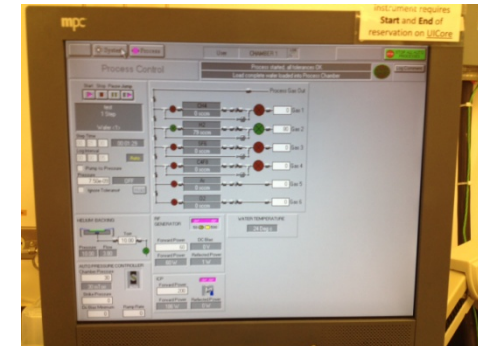
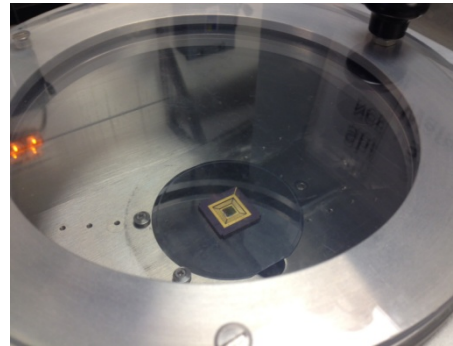
- Statistically significant improvements
- Stability tested over several months
- G-R and shunt components of dark current have been reduced
- Surface passivation improved



## ICP schematic diagram



- ICP ensures a high plasma density with a high density of atomic hydrogen at low operating pressures
- Additional bias can be applied to prevent ionized species from penetrating the sample



## Approach

- Our goal: Advance T2SL materials technology by passivating lifetime-limiting defects with H.
- Use ICP-generated atomic and ionized H diffused into T2SL films to passivate defects.
- Measure material properties (carrier mobility and lifetime) before and after ICP hydrogenation.

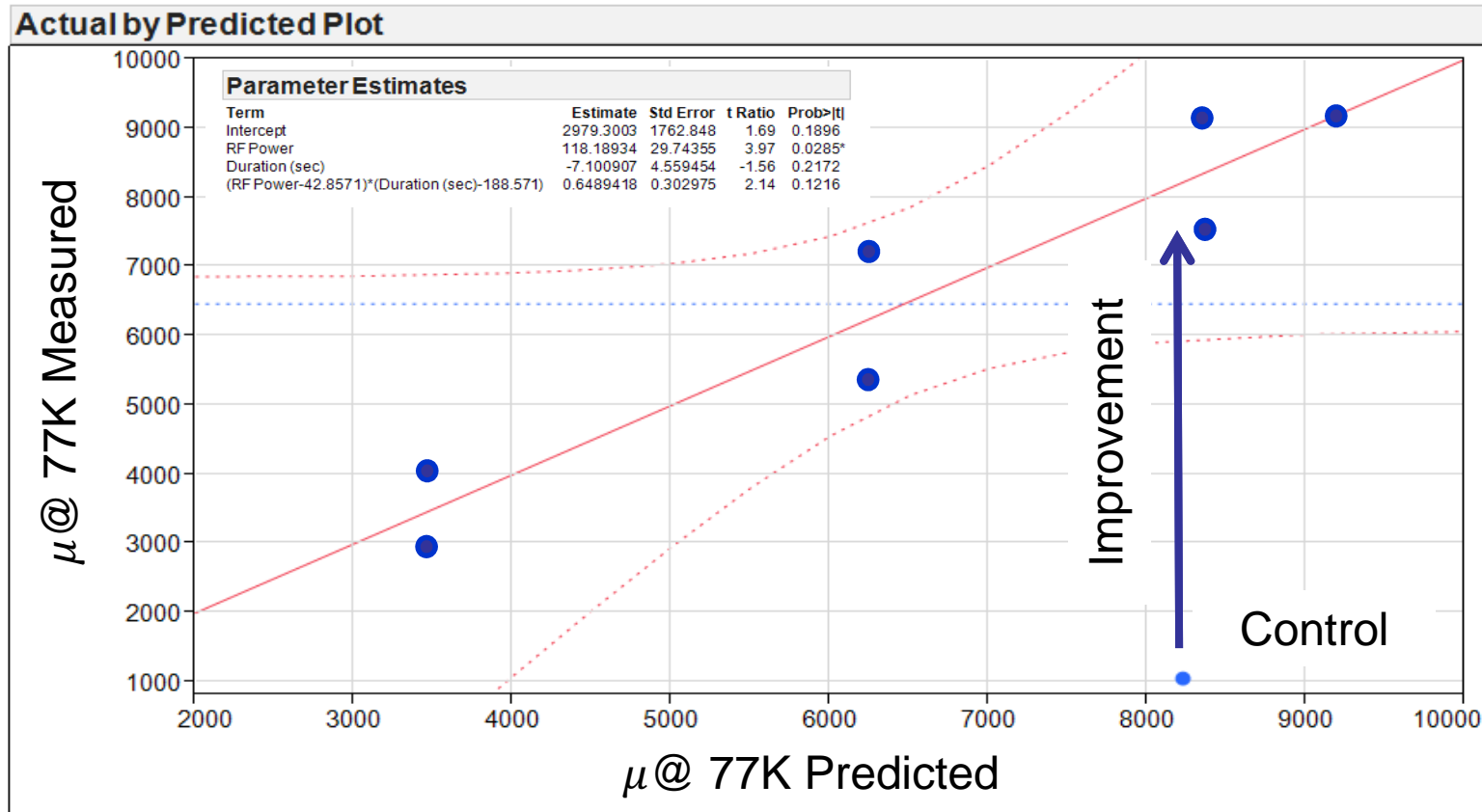
## Figures of Merit

- **Material-level metrics**
  - Minority carrier lifetime
  - Majority carrier mobility
- **Photodiode-level metrics**
  - I-V dark current – g/r, TAT, BTBT, diffusion
  - C-V sweeps - mobile charges, interface  $n$
- **FPA-level metrics**
  - Noise equivalent temperature difference distribution
  - Pixel operability distribution





# Preliminary T2SL Hydrogenation Results



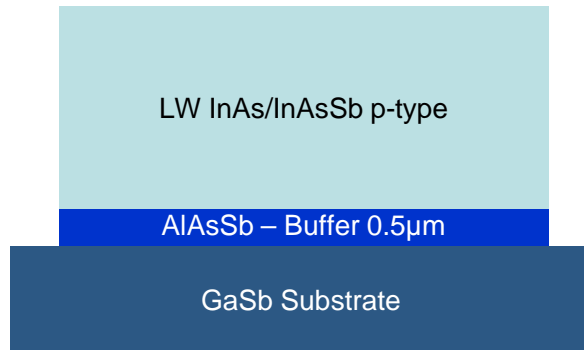
- Mobility increases with hydrogenation (79% adjusted  $R^2$ )
- Entirely a function of RF power and duration
  - Higher power, lower duration yields better  $\mu$
- Control sample shows far lower mobility



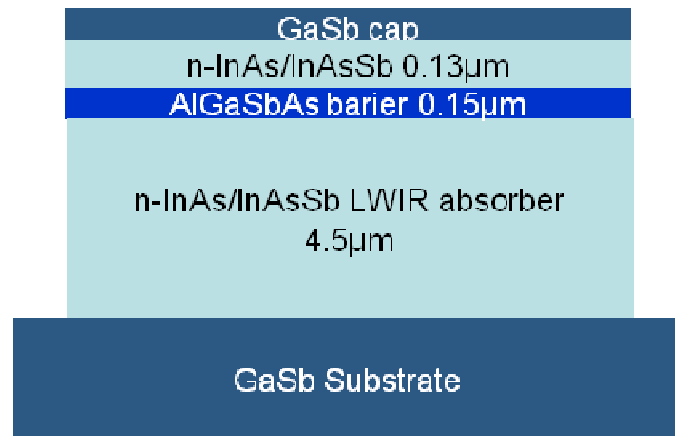
# LWIR T2SL Material



4  $\mu\text{m}$  99Å InAs/34 Å InAs<sub>0.59</sub>Sb<sub>0.41</sub>,  $p \sim 10^{15} \text{ cm}^{-3}$

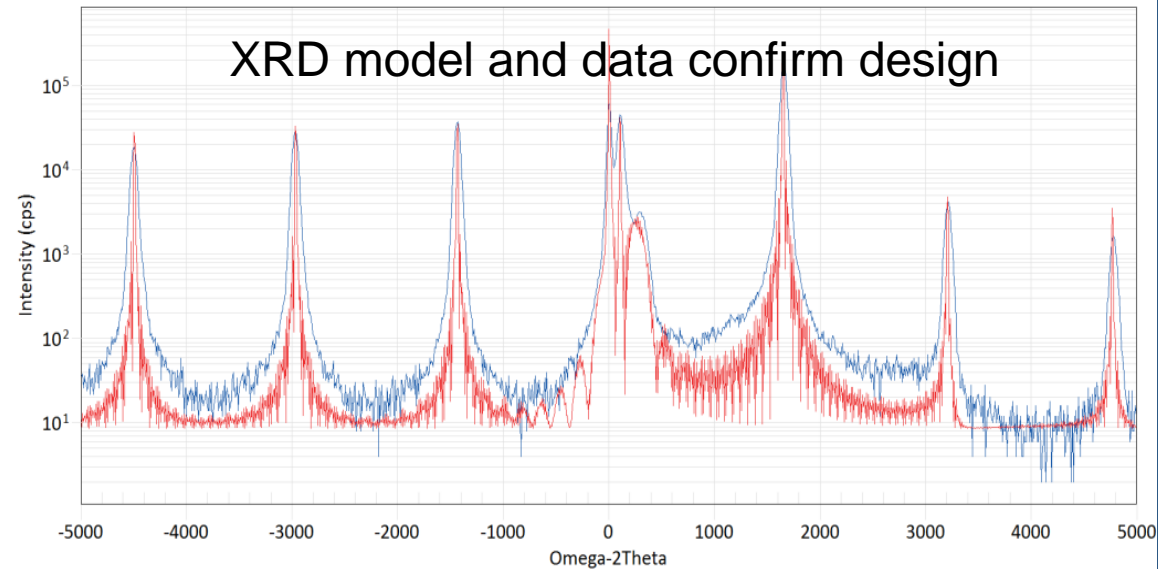


Acquired from IntelliEpi

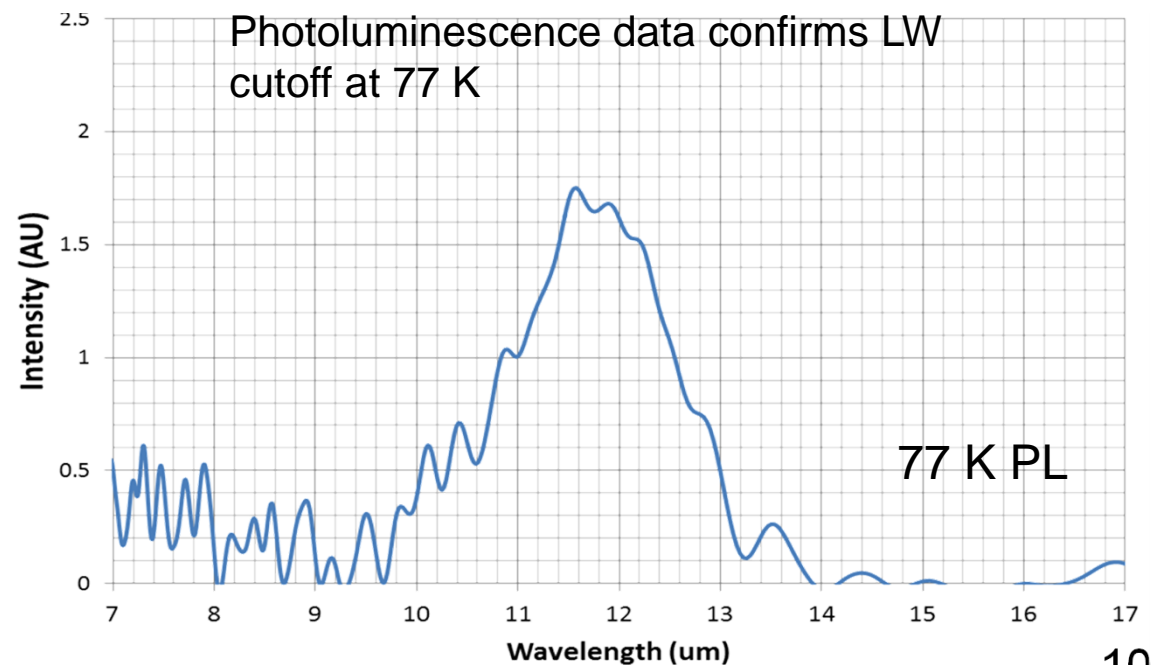


JPL-provided nBn detector structures

XRD model and data confirm design

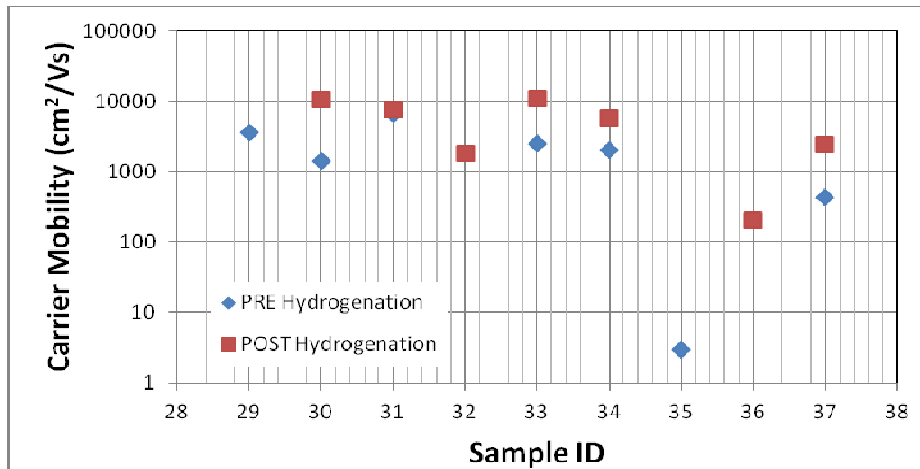


Photoluminescence data confirms LW cutoff at 77 K



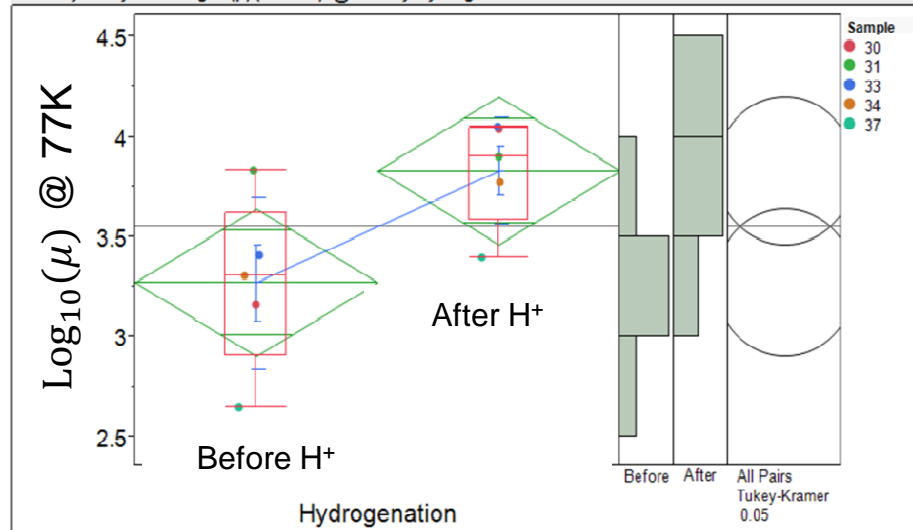


# In-plane 77K Hall Mobility

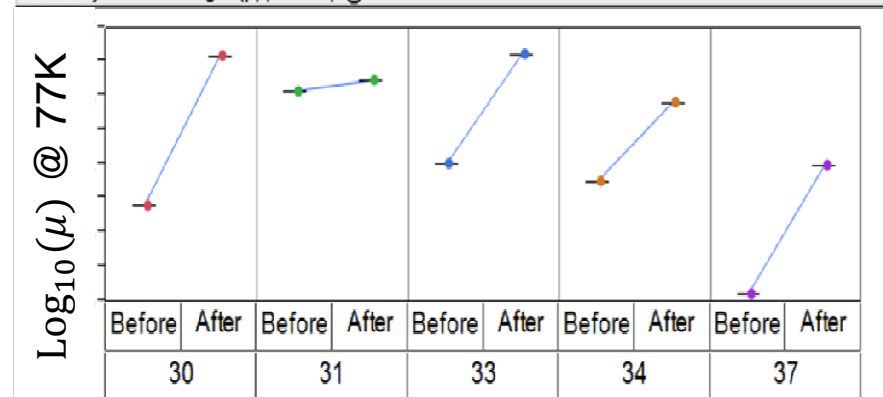


Largest increases following hydrogenation from samples with lowest initial mobility values

Oneway Analysis of Log10 ( $\mu$ ) (cm²/Vs) @77 K By Hydrogenation



Variability Chart for Log10 ( $\mu$ ) (cm²/Vs) @77 K



On average, mobility measured post-hydrogenation increased from 1800 cm²/Vs to 6800 cm²/Vs, a relative increase of over 300%

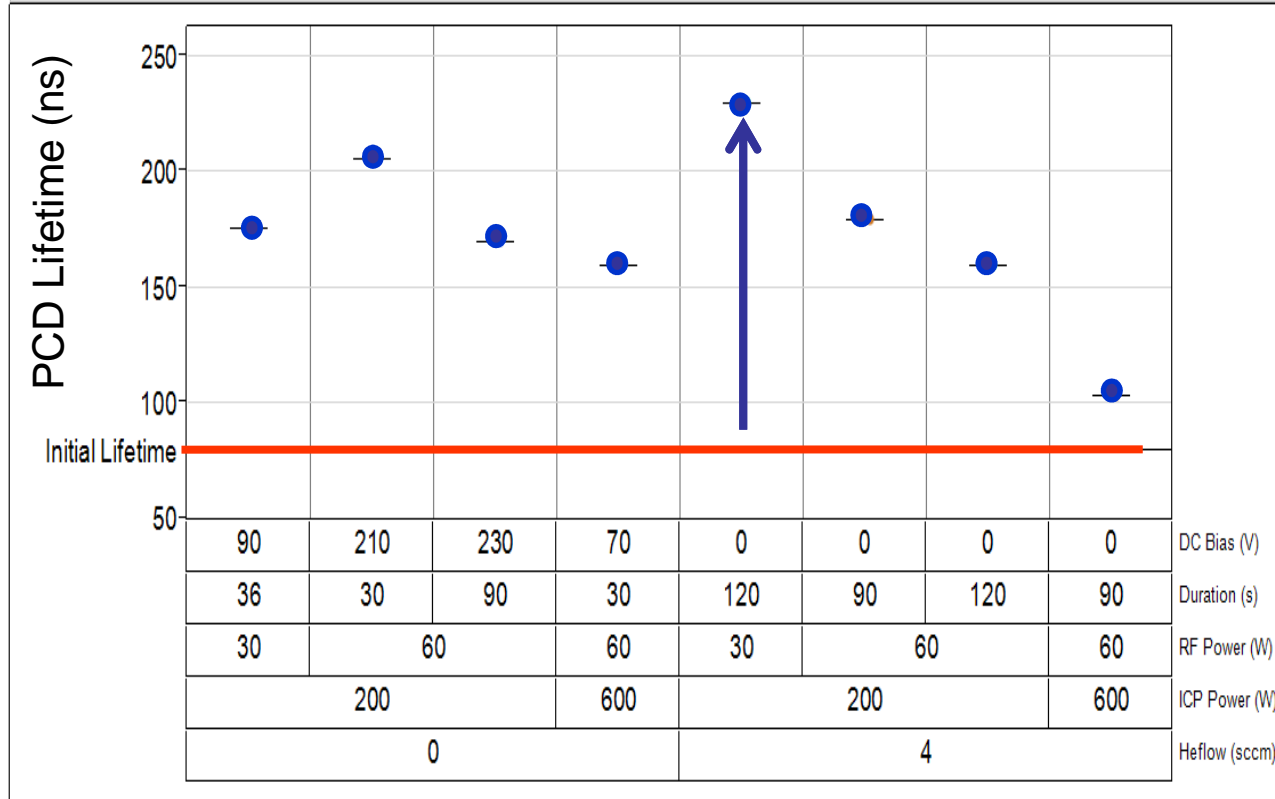
- Is statistically significant



# Minority Carrier Lifetimes



Variability Chart for Lifetime (ns)



Improved Hall mobilities following hydrogenation treatment using **same** plasma parameters that resulted in largest minority carrier lifetime increases

- ICP hydrogenation improved minority carrier lifetime for **each** of the ICP conditions explored
- Lifetime values have increased on the average from 80 ns, before hydrogenation, to over 200 ns, a relative increase of over 200%



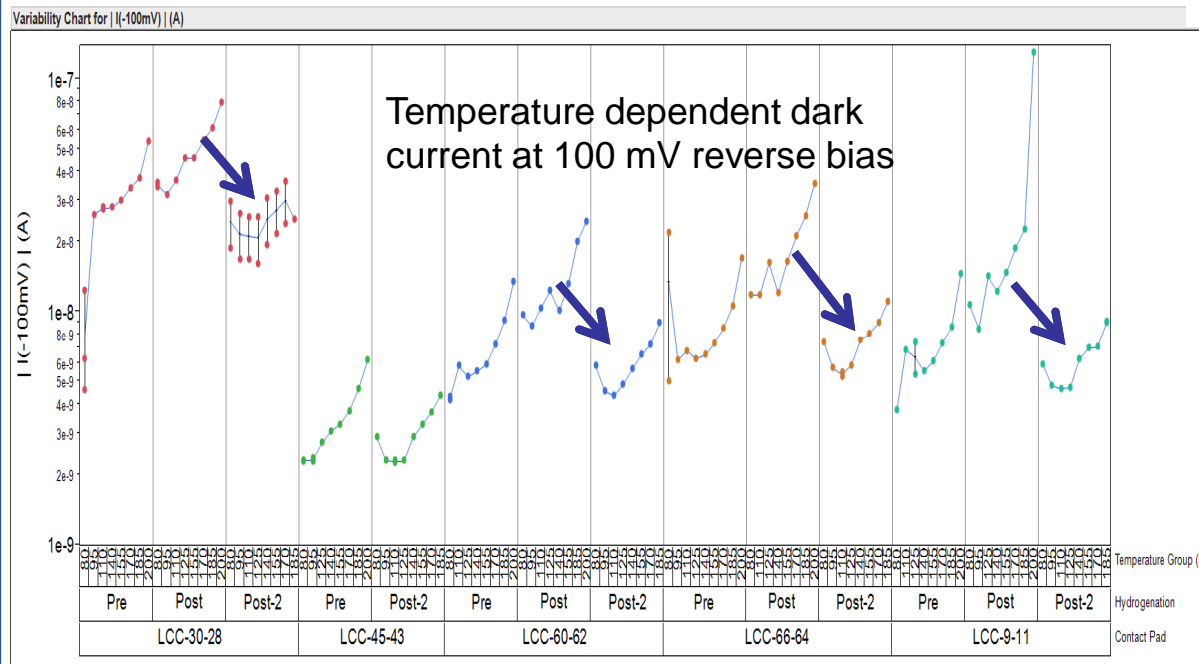
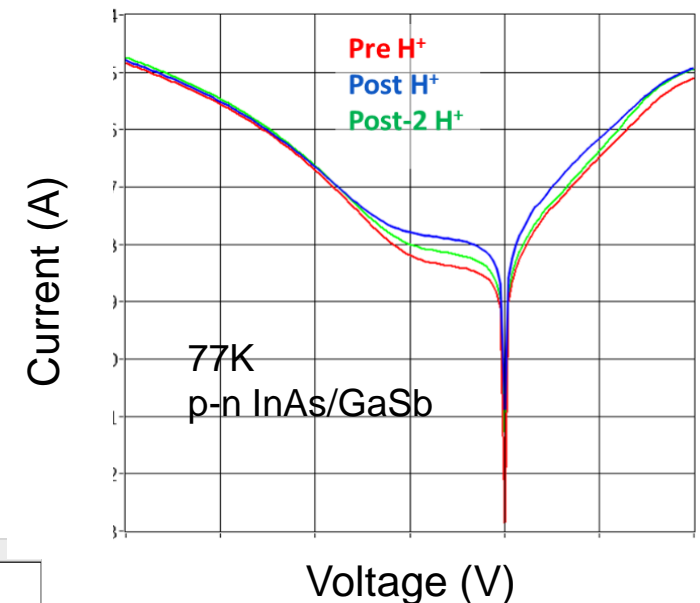
# Dark Current Preliminary Study



Same photodiodes exposed twice

Hydrogenation 1: Lower DC biases – surface deterioration  
Un-optimized process

Hydrogenation 2: Improved surface morphology  
Improved dark current



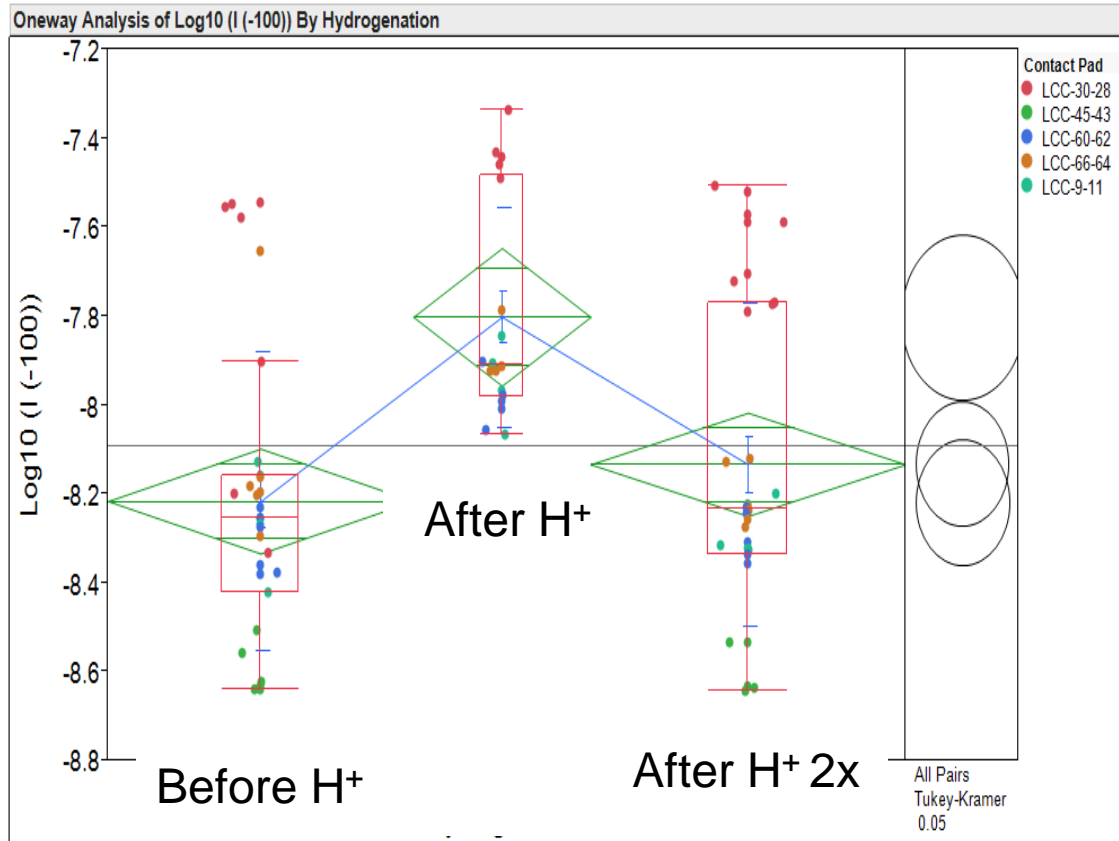
ICP hydrogenation generates competing outcomes

Additional optimizations and trade-off studies required to enhance desired outcomes

Devices passivated with thioacetamide (TAM)



# Statistical Analysis of Dark Currents



Although not optimal, the second ICP recipe is more beneficial than it is detrimental and has the potential to “repair” the material

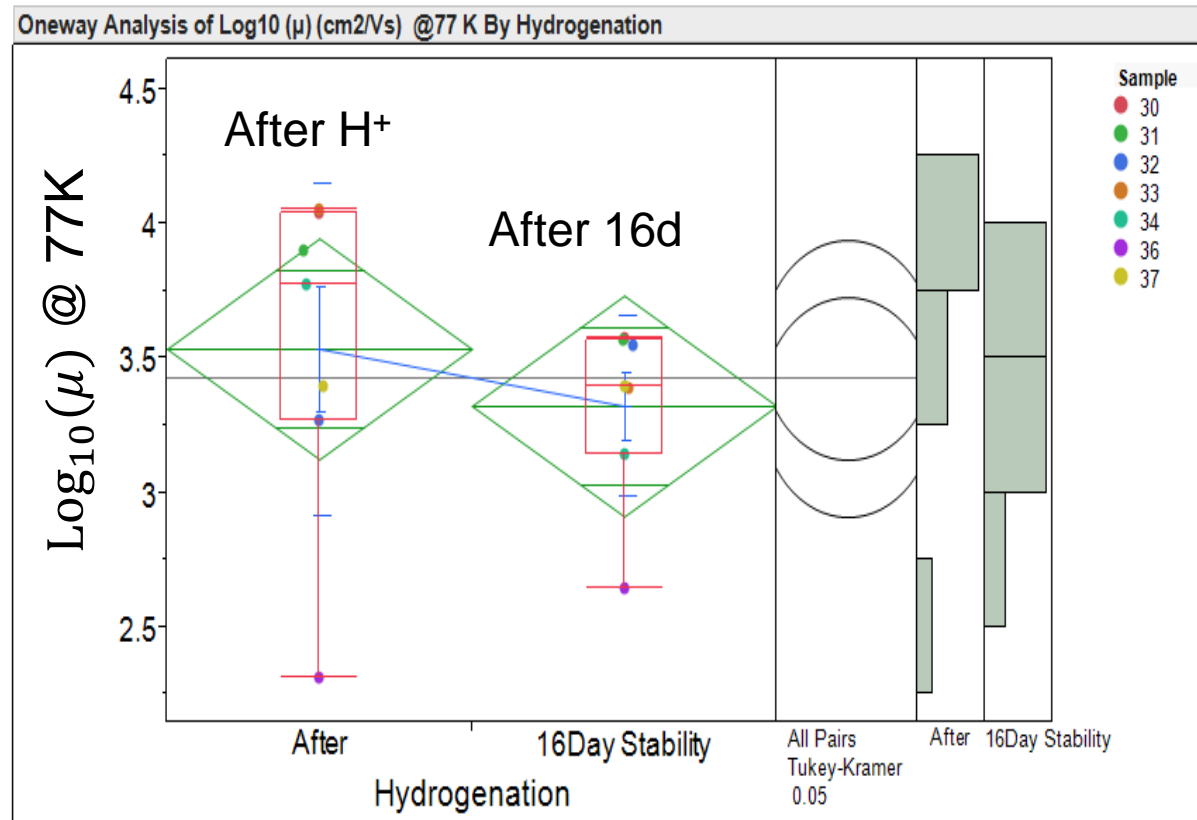
Hydrogenation 2: same parameters produce largest mobility improvements measured on wafers

**Some diodes were unaffected by ICP: contain different classes of defects**

Second hydrogenation recipe has the potential to passivate at least some of material imperfections in general, not only those generated by an imperfect hydrogenation process



# Mobility Stability of Hydrogenated T2SL



- In-plane 77 K Hall mobility
- Short term stability tested
- Room temperature storage
- No significant changes over couple of weeks





# Summary



- ICP hydrogenation is a promising technique to advance state of the art large format T2SL FPAs
- At least partial passivation of recombination-mediating defects in T2SLs has been demonstrated (average ~200% increase in lifetime)
- Same ICP parameters increase in-plane mobility (average ~300% increase in 77K Hall mobility), and is stable over tested periods
- ICP hydrogenation has both beneficial and detrimental effects: need to further optimize



# Potential Future Research



- Determine efficacy of hydrogen passivating various classes of defects (extended defects, localized defects, etc.)
- Explore and identify mechanisms of hydrogen diffusion
  - Exploit them to enhance retention of passivant and diffusion into desired locations, such as lateral diffusion to reach underneath metals in existing photodiodes
- Determine effect of hydrogen passivation on dopants and their electrical activity
- Determine the optimized plasma conditions for efficient passivation
- Explore the most suitable FPA fabrication step at which hydrogen passivation should be undertaken
- Explore long-term retention of hydrogenation benefits